

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

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INFORMATION DISCLOSURE
STATEMENTDocket Number
20103 00201Application Number **10/069656**
To be assigned Filing Date
Herewith

Examiner

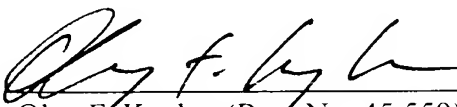
Art Unit

Invention Title
**DEVICE FOR FORMING NANOSTRUCTURES
ON THE SURFACE OF A SEMICONDUCTOR
WAFER BY MEANS OF ION BEAMS**Inventor(s)
SMIRNOV et al.Address to:
Commissioner for Patents
P.O. Box 2327
Arlington, VA 22202

1. In accordance with the duty of disclosure under 37 C.F.R. § 1.56 and in conformance with the procedures of 37 C.F.R. §§ 1.97 and 1.98 and M.P.E.P. § 609, attorneys for Applicants hereby bring the following reference (cited in the specification of the above-identified application) to the attention of the Examiner. The reference is listed on the attached modified PTO Form No. 1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference be made of record therein and appear among the "Reference Cited" on any patent to issue therefrom.
2. A copy of each patent, publication or other information listed on the modified PTO form 1449 is enclosed.

Dated: Feb. 25, 2002

By:


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INFORMATION DISCLOSURE STATEMENT BY APPLICANT FORM PTO-1449	ATTY. DOCKET NO. 20103 00201	SERIAL NO. 10/089656 To be assigned
	APPLICANT(S) SMIRNOV et al.	
	FILING DATE Herewith	GROUP

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE*

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE (M D Y)	COUNTRY	CLASS	SUBCLASS	CITATION	
						YES	NO
	EP 0275965	July 27, 1988	EPO			N A	

OTHER DOCUMENTS

EXAMINER INITIAL		AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.

EXAMINER	DATE CONSIDERED
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	